

Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 10559-865001	Application No. 10/649,355
<b>Information Disclosure Statement by Applicant</b> (Use several sheets if necessary) (37 CFR §1.98(b))		Applicant Florence Eschbach et al.	
		Filing Date August 26, 2003	Group Art Unit 1713 <i>H.H.</i>

## U.S. Patent Documents

Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
<i>H.H.</i>	AA	2001/0004508	06/2001	Shirasaki			
	AB	2001/0014375	08/2001	Tanaka			
	AC	2002/0136965	09/2002	Tsumoto et al.			
	AD	2002/0179852	12/2002	Zheng et al.			
	AE	2003/0096178	05/2003	Fujita et al.			
	AF	2003/0187168	10/2003	Sunaga et al.			
	AG	2003/0192567	10/2003	Koizumi et al.			
	AH	2004/0123950	07/2004	Boyd			
	AI	2005/0045262	03/2005	Eschbach et al.			
	AJ	2005/0202252	09/2005	Tregub et al.			
	AK	2005/0203254	09/2005	Tregub et al.			
	AL	4,060,654	11/1977	Quenneville			
	AM	5,378,514	01/1995	Hamada et al.			
	AN	5,643,654	07/1997	Fujita et al.			
	AO	5,723,860	03/1998	Hamada et al.			
	AP	5,880,204	03/1999	McCarthy et al.			
	AQ	6,055,040	04/2000	Sego			
	AR	6,083,577	07/2000	Nakagawa et al.			
	AS	6,111,062	08/2000	Shirota et al.			
	AT	6,436,586	08/2002	Matsuoka et al.			
	AU	6,524,754	02/2003	Eynon			
	AV	6,639,650	10/2003	Shirasaki			
	AW	6,652,958	11/2003	Tobita			
	AX	6,822,731	11/2004	Laganza et al.			
	AY	6,841,312	01/2005	Kalk			
	AZ	6,842,227	01/2005	Shu			
✓	BA	6,842,228	01/2005	Shu			

Examiner Signature <i>[Signature]</i>	Date Considered <i>8-24-06</i>
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

Substitute Form PTO-1449 (Modified)  <b>Information Disclosure Statement by Applicant</b> (Use several sheets if necessary)  (37 CFR §1.98(b))	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 10559-865001	Application No. 10/649,355
	Applicant Florence Eschbach et al.		
	Filing Date August 26, 2003	Group Art Unit 1713 <i>H.Hu</i>	

U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
<i>H.Hu</i>	BB	6,869,733	03/2005	Su			
	BC						

Foreign Patent Documents or Published Foreign Patent Applications								
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
<i>H.Hu</i>	BD	0 438 602	07/1991	Europe				
	BE	0 529 827	03/1993	Europe				
	BF	0 942 325	09/1999	Europe				
	BG	09-005982	01/1997	Japan				
	BH	2005/022259	03/2005	WIPO				
	BI							

Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
<i>H.Hu</i>	BJ	Chen, et al., "Pellicle-Induced Reticle Distortion: An Experimental Investigation", <i>Proc. of SPIE - The Int'l Soc. for Optical Engineering</i> , Vol. 3546, pp. 167-172 (1998).
	BK	Cotte, et al., "Effects of Soft Pellicle Frame Curvature and Mounting Process on Pellicle-Induced Distortions in Advanced Photomasks", <i>Proc. of SPIE - The Int'l Soc. for Optical Engineering</i> , Vol. 5040, pp. 1044-1054 (2003).
	BL	Cotte, et al., "Experimental and Numerical Studies of the Effects of Materials and Attachment Conditions on Pellicle-Induced Distortions in Advanced Photomasks", <i>Proc. of SPIE - The Int'l Soc. for Optical Engineering</i> , Vol. 4754, pp. 579-588 (2002).
	BM	Cotte, et al., "Numerical and Experimental Studies of Pellicle-Induced Photomask Distortions", <i>Proc. of SPIE - The Int'l Soc. for Optical Engineering</i> , Vol. 4562, pp. 641-651 (2002).
	BN	Karis, et al., "Characterization of a solid fluorocarbon film on magnetic recording media", <i>J. Vac. Sci. Technol. A</i> , 15(4):2382-2387, (1997).
	BO	Karis, et al., "Tribology of a Solid Fluorocarbon Film on Magnetic Recording Media", <i>IEEE Transactions on Magnetics</i> , 34(4):1747-1749, (1998).
	BP	LaPedus, M., "Nikon evaluating 157-nm lithography options", <i>EE Times UK</i> , <a href="http://www.eetuk.com/tech/news/dev/OEG20030523S0061">http://www.eetuk.com/tech/news/dev/OEG20030523S0061</a> , May 24, 2003.
	BQ	Resnick & Buck, "Teflon® AF Amorphous Fluoropolymers", <i>Modern Fluoropolymers</i> , Edited by J. Schews, John Wiley & Sons, Inc., pp. 397-419, (1997).
	BR	Seki, et al., "Electronic Structure of Poly(tetrafluoroethylene) Studied by UPS, VUV Absorption, and Band Calculations", <i>Physica Scripta</i> , 41(1):167-171, (1990).
	BS	Singer, P., "Atomic Layer Deposition Targets Thin Films", <i>Semiconductor International</i> , 22(10):40, (1999).

Examiner Signature <i>H.Hu</i>	Date Considered <i>8-24-06</i>
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 10559-865001	Application No. 10/649,355
<b>Information Disclosure Statement by Applicant</b> (Use several sheets if necessary) (37 CFR §1.98(b))		Applicant Florence Eschbach et al.	
		Filing Date August 26, 2003	Group Art Unit 1713 <i>HHy</i>

Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
<i>HHy</i>	BT	Sugiyama, "Perfluoropolymers Obtained by Cyclopolymerization and Their Applications", <u>Modern Fluoropolymers</u> , Edited by J. Schews, John Wiley & Sons, Inc., pp. 541-555, (1997).
<i>↓</i>	BU	Theirich, et al., "A novel technique for high rate plasma polymerization with radio frequency plasmas", <u>Surface and Coatings Technology</u> , 86-87, pp. 628-633, (1996).
<i>↓</i>	BV	Walton, K.R., "The Lubrication of Gold Surfaces by Plasma-Deposited Thin Films of Fluorocarbon Polymer," <u>IEE Transactions on Components, Hybrids, and Manufacturing Technology</u> , CHMT-3(2):297-304, (1980).
	BW	

Examiner Signature <i>JL</i>	Date Considered <i>8-24-06</i>
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	